SENTECH
Erfolg durch Leistung

Experts in Plasma Process Technology and Thin Film Metrology

SEMINAR:
Plasma Process Technology

NETWORKING DINNER

At 19:00 Restaurant IL Porto
Semmelweisstrasse 104a, Berlin-Adlershof
On Wednesday evening, May 14, 2025

Location of the PLASMA SEMINAR:

SENTECH Instruments GmbH
Schwarzschildstrasse 2, Berlin-Adlershof
On Thursday, May 15, 2025

SEMINAR PROGRAM

09:00 **Welcome and introduction of the program, organisation, and SENTECH employees**
Friedrich P. Witek, SENTECH GmbH, Krailling and SENTECH Instruments GmbH, Berlin

Etching:

09:10 **SENTECH Plasma Process Technology –**
Latest developments in etching of SiC, III-V compounds, and stress-controlled ICPECVD
Marcel Schulze, SENTECH Instruments GmbH, Berlin
Friedrich P. Witek, SENTECH GmbH, Krailling and SENTECH Instruments GmbH, Berlin

09:40 **Diamond nanophotonics for applications in quantum technology**
Tim Schröder, Humboldt-Universität zu Berlin, Institut für Physik, Berlin, Germany

10:10 ***Coffee break and time for discussions***

10:45 **Hybrid material platforms for advanced nanophotonics applications**
Andrew Docherty, University of St Andrews, Scotland, United Kingdom

11:15 **To be confirmed: Deep reactive ion etching of Si**
Thomas Siefke, Friedrich-Schiller-Universität Jena, Institut für Angewandte Physik IAF, Jena, Germany

11:45 **Atomic Layer Etching of SiO_2 using sequential SF_6 gas and Ar plasma**
Rakshith Venugopal, Universität Hamburg, Zentrum für Hybride Nanostrukturen, Hamburg, Germany

12:15 ***Lunch and time for discussions***

Deposition:

13.45 **Advancements in ALD Layers for GaN-based electronic devices**
Eldad Bahat-Treidel, Ferdinand-Braun-Institut gGmbH, Leibniz-Institut für Höchstfrequenztechnik, Berlin, Germany

14:15 **Low-temperature ALD process sequences for flexible 2D electronics based on MoS_2 ***
Julia Jagosz, SENTECH Instruments, Berlin
* Dissertation at Ruhr-Universität Bochum, Fakultät für Elektrotechnik und Informationstechnik, Lehrstuhl für Mikrosystemtechnik, Bochum, Germany

14:45 ***Coffee break and time for discussions***

15:20 **ICPECVD high-performance dielectrics: Processing, properties and applications**
Rachid Driad, Fraunhofer-Institut für Angewandte Festkörperphysik IAF, Freiburg, Germany

15:35 **Comparison of True Remote CCP source and Planar Triple Spiral Antenna ICP source for PEALD**
Paul Plate / Ludwig Marth, SENTECH Instruments GmbH, Berlin, Germany

15:50 **Deep etching of Si using electrostatic chucking for enhanced process performance**
Thomas Tatry, SENTECH Instruments GmbH, Berlin, Germany

16:30 **All participants of the seminar are invited to visit the application laboratories at SENTECH Instruments**

17:30 **End of the seminar**

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